

ABSTRACT OF THE DISCLOSURE

The invention provides an improvement in a pellicle container for containing a framed pellicle conventionally made from a plastic resin, which is mounted on a photolithographic photomask for dust-proof protection thereof. A serious problem in the plastic resin-made container is adsorption or deposition of organic matters emitted from the container body by or on the pellicle membrane during storage or transportation resulting in a decrease in the light transmission as well as accelerated degradation of the pellicle membrane to the light of an extremely short wavelength for patternwise exposure in the photolithography while this problem can be solved by the improvement of the invention according to which at least the surface layer of the container surfaces facing the space for containing the framed pellicle is formed from an inorganic material, e.g., metals, glass materials and ceramics, free from emission of any organic matters.